

- More than bil
- □ Viewing angle ■ Strong sensal
- □ Natural and d ☐ Calculation b
- □ Print by laser The Venus
- 4 G Pix (64K×64K) Opt. 48, H54-H63 (2009)

45° in horizontal and vertica

n of depth tinuous motion parallax he polygon-based method

riter & lithography 8 G Pix (128K×64K)

K. Matsushima, H. Nishi, S. Nakahara, J. Electron, Imaging 21, 023002 (2012)



Nishi, K. Matsushima, S. Nakahara, Appl. Opt. 50, H245-H252 (2011)



G Pix (64K×64K) 8281, 828110 (2012)

Matsushima, S. Nakahara,

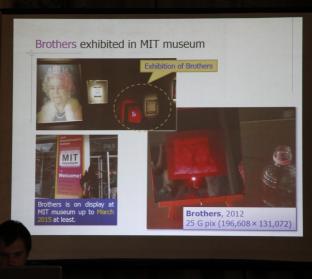


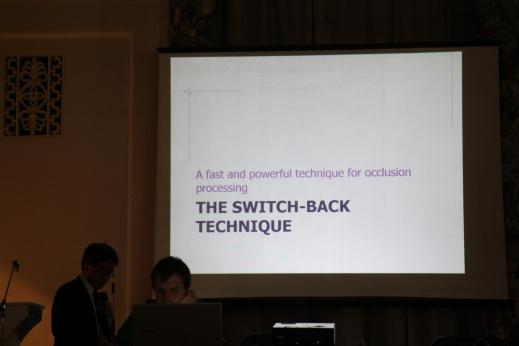
K. Matsushima, Y. Arima, S. Nakahara, K. Matsushima, M. Nakamura, S. Nakahara, Appl. Opt. 50, H278-H284 (2011)

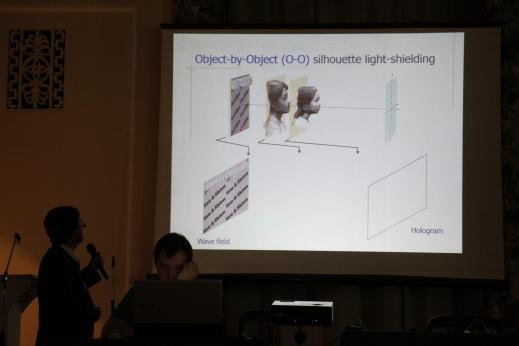


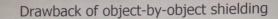
4 G Pix (64K×64K)

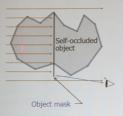
Opt. Express 22, 24450 (2014)



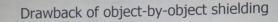


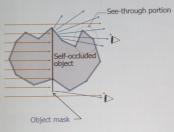




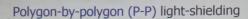


- If the object have self-occlusion, there may be see-through potion. In this case viewer may see partial phantom image.
- Object-by-object shielding cannot be applied to complicated-shape objects.
 This problem is resolved by shielding polygon-by-polygon.



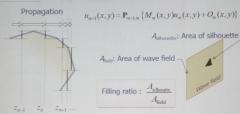


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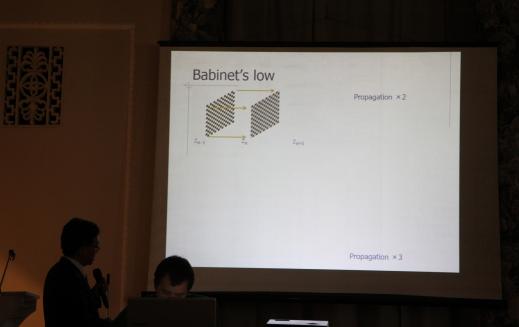


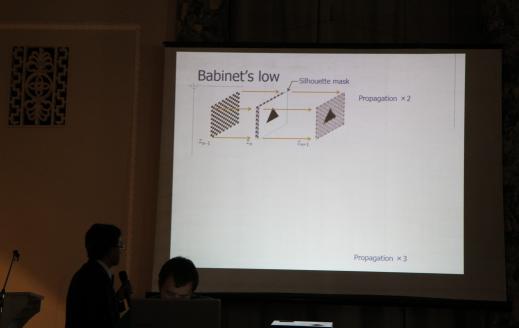
A_{silhouette}: Area of silhouette

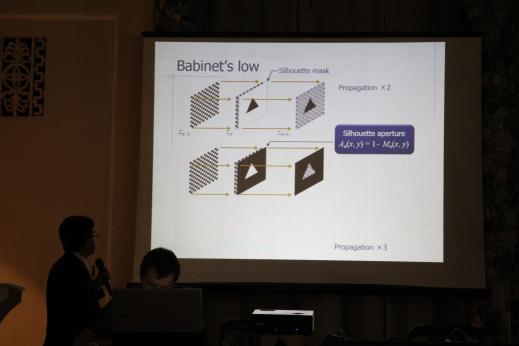
 $A_{\rm field}$

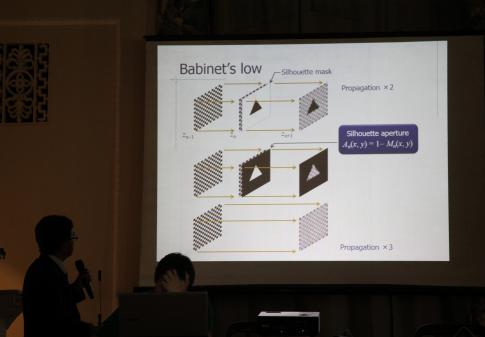


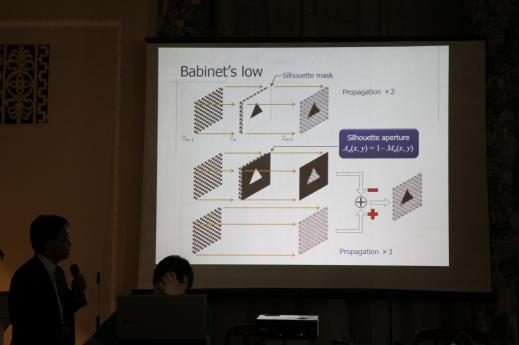
Shielding unit	Number of masks	Size of silhouette (Filling ratio)	Distance between silhouettes
Object-by-object	1~10	Large (10~80%)	Long
Polygon-by-polygon	100~ 100,000	Very small (0.01~10%)	Short

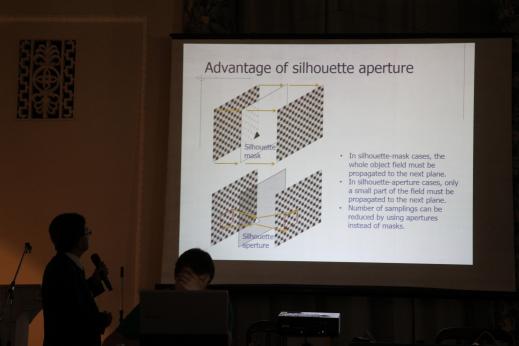


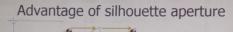


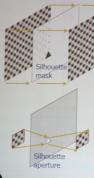




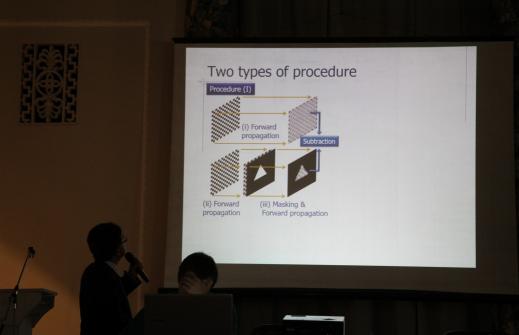


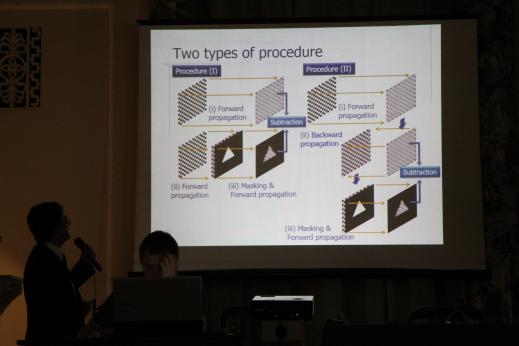


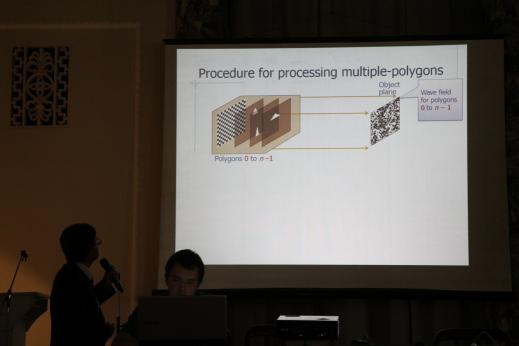


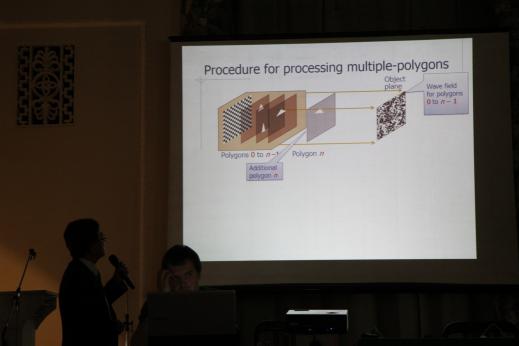


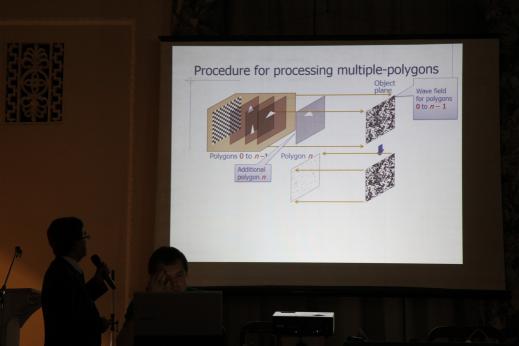
- In silhouette-mask cases, the whole object field must be propagated to the next plane.
- In silhouette-aperture cases, only a small part of the field must be propagated to the next plane.
- Number of samplings can be reduced by using apertures instead of masks.



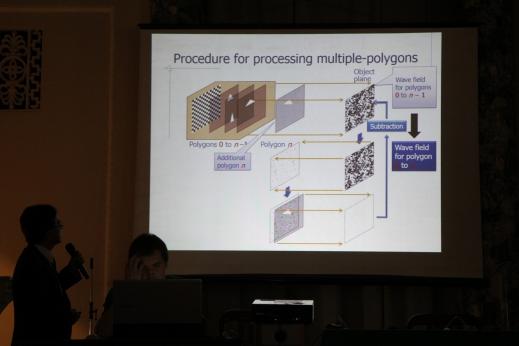


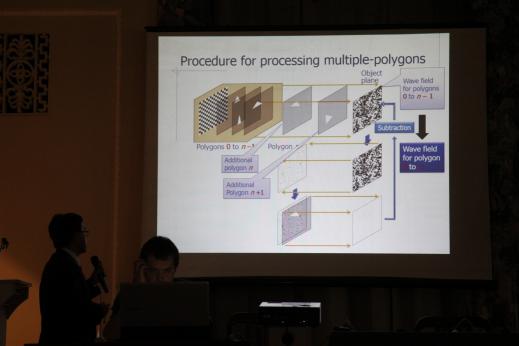


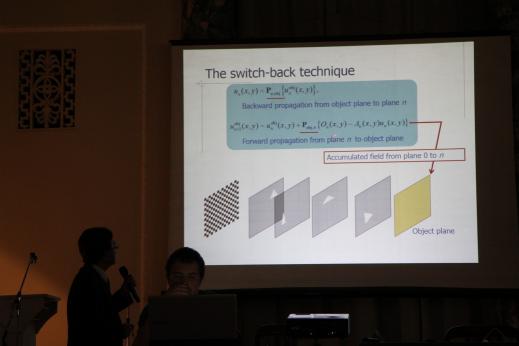


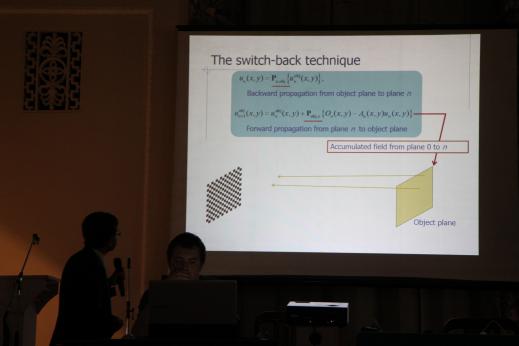


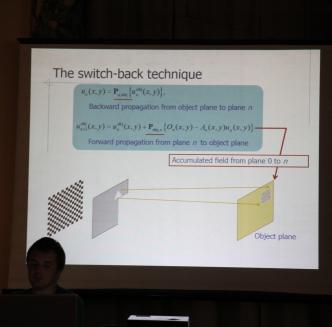
Procedure for processing multiple-polygons Object plane Wave field for polygons 0 to n - 1 Polygons 0 to n-1 Polygon n Additional polygon n

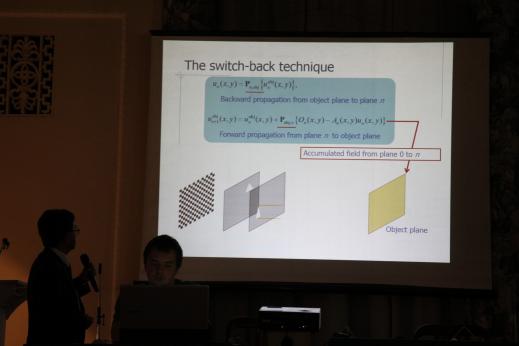


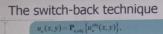












$$u_n(x,y) = \mathbf{P}_{n,\text{obj}} \left\{ u_n^{\text{obj}}(x,y) \right\},\,$$

Backward propagation from object plane to plane n

$$u_{n+1}^{\text{obj}}(x,y) = u_n^{\text{obj}}(x,y) + \mathbf{P}_{\text{obj},n} \{ O_n(x,y) - A_n(x,y) u_n(x,y) \} -$$

Forward propagation from plane n to object plane

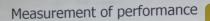
Accumulated field from plane 0 to n

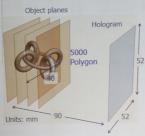






The procedure is called switch-back technique, because field is propagated back and forth.





Indicated sizes are of the full-size model.

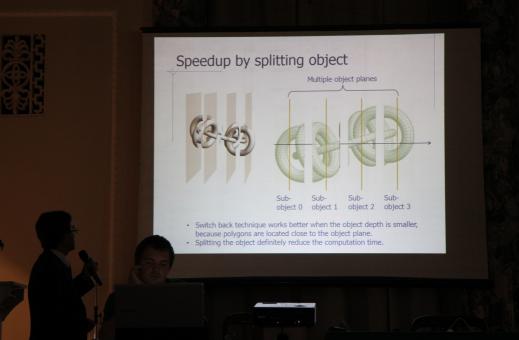
Pixel pitch: 0.8 μm × 0.8 μm Wavelength: 633 nm

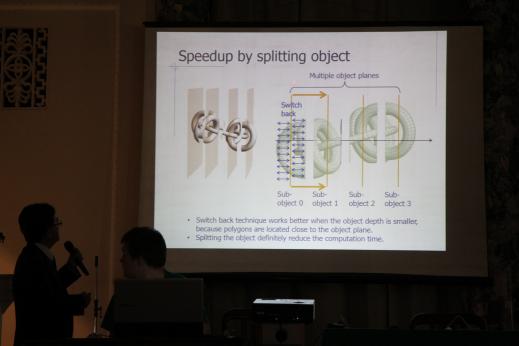
1K = 1024

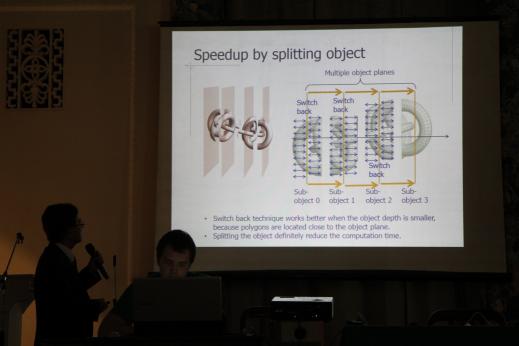
This CGH is on display in the back of this room

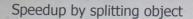


Model	No. of pixels	
Full-size	64K×64K (4.3×10°)	
1/32 scale	$2K \times 2K (4.2 \times 10^6)$	



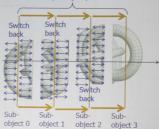






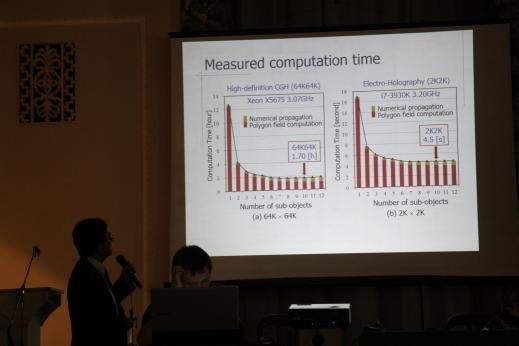
Multiple object planes

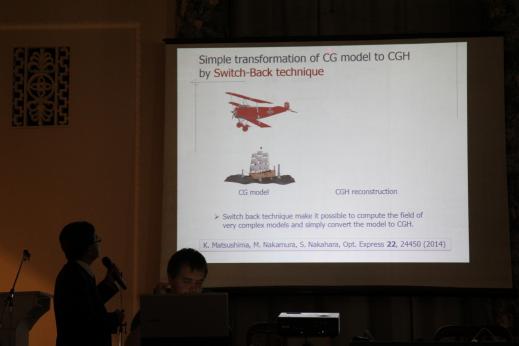


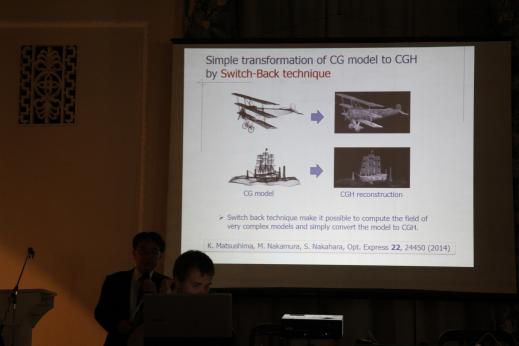


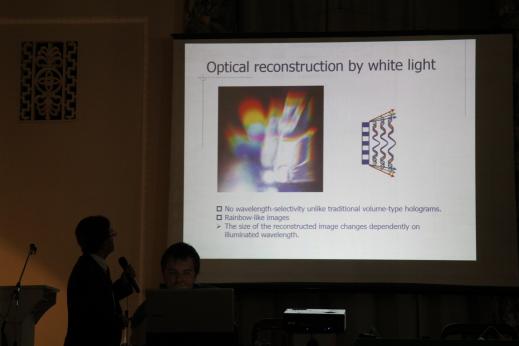
- Switch back technique works better when the object depth is smaller, because polygons are located close to the object plane.
- · Splitting the object definitely reduce the computation time.

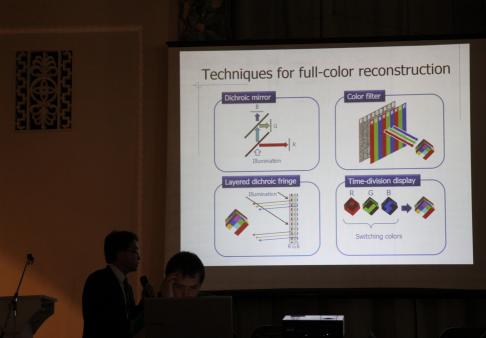
Measured computation time Electro-Holography (2K2K) High-definition CGH (64K64K) i7-3930K 3.20GHz Xeon X5675 3.07GHz [puo 14 12 12 Computation Time [hour] Numerical propagation Polygon field computation Numerical propagation Polygon field computation Computation Time 2K2K 4.5 [s] 64K64K 1.70 [h] Number of sub-objects Number of sub-objects (a) 64K × 64K (b) 2K × 2K

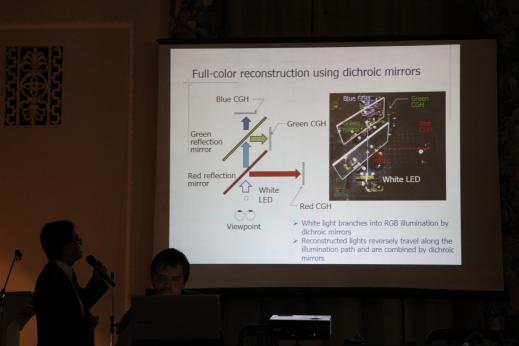


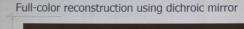






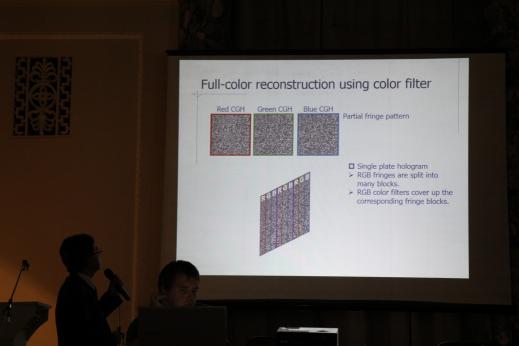


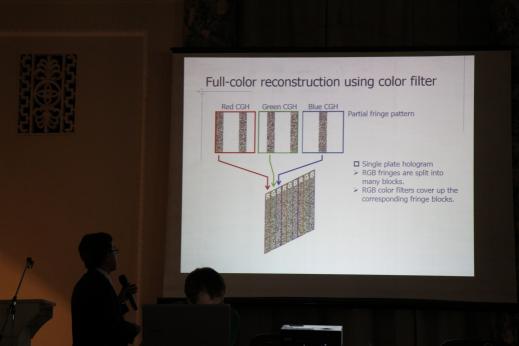


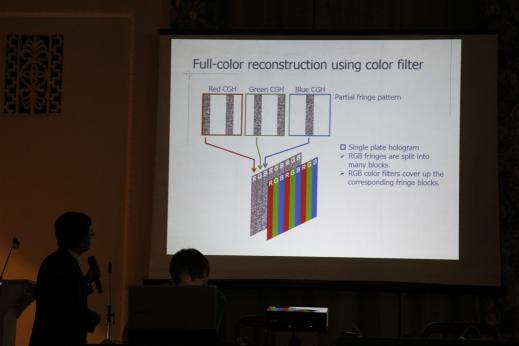


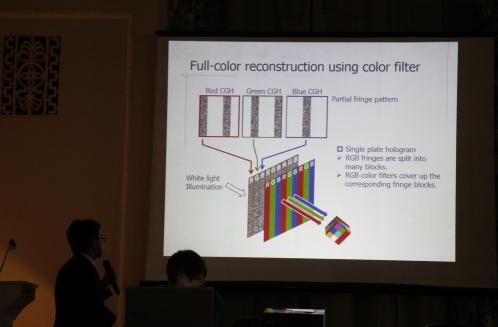


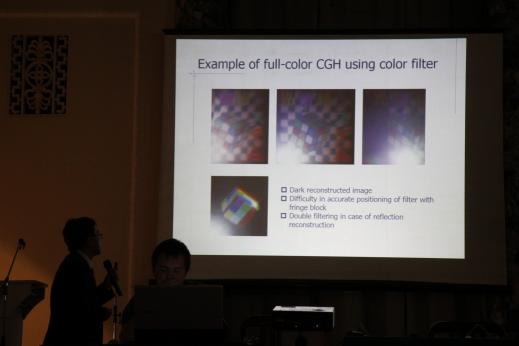
- □ Very good optical reconstruction
- No portability
- > Optical system for superposition is complicated, heavy and expensive.







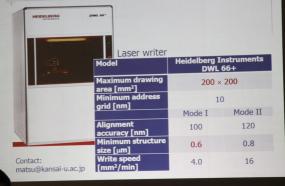


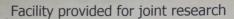






Facility provided for joint research







Printing is free of charge

You must provide fringe pattern generated by yourself

Laser writer		
Model	Heidelberg Instruments DWL 66+	
Maximum drawing area [mm²]	200 × 200	
Minimum address grid [nm]	10	
	Mode I	Mode II
Alignment accuracy [nm]	100	120
Minimum structure size [µm]	0.6	0.8
Write speed [mm²/min]	4.0	16

Contact: matsu@kansai-u.ac.jp

